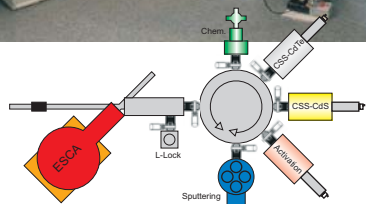
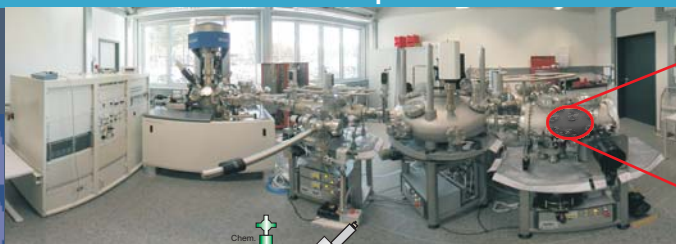


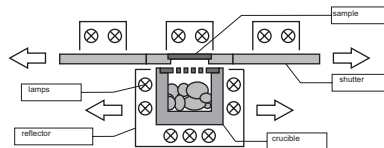
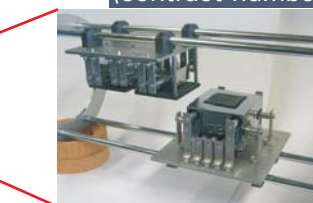
# Integrated Systems for Solar Energy Research: First Results with DAISY-SOL

## I. DAISY-SOL-Setup

supported by the Federal Ministry for the Environment  
(contract number: 0329857A)



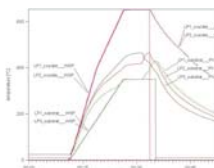
- all in-situ solar cell manufacturing
- 2 dynamic CSS-chambers
- UHV-activation (in construction)
- backcontact formation (evaporation, sputtering)
- in-situ XPS/UPS-characterisation



CSS-deposition-unit, schematic

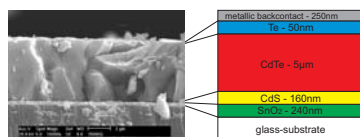
### DAISY-SOL-CSS: Properties

- + dynamic deposition (close to industrial manufacturing)
- + high rates of deposition (up to 10µm/min)
- + high substrate temperatures (up to 600°C)
- + homogeneous layers
- + only 2mm distance substrate/crucible
- + difficult temperature control
- high CdTe-consumption (1g/layer)



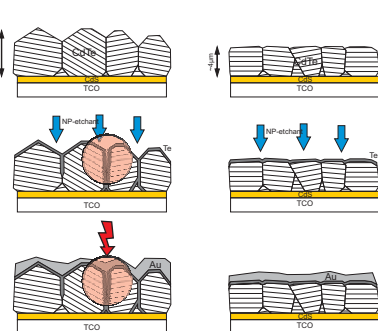
temperature-profile, CdTe-deposition

## II. Investigations on Nucleation and Growth

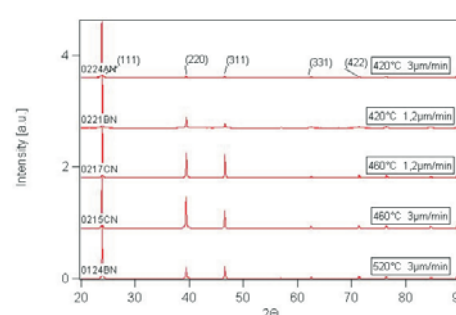


### Requirements

At the present state CdTe-solar cells deposited with CSS-technique exhibit very large grains (>5µm) with high surface roughness (R<sub>ms</sub>>300nm). This usually leads to the formation of shunts during the activation process, etching and backcontact deposition. To avoid this, the CdTe-layer has to be thicker than 8µm, which is correlated with high efficiency losses due to a high series resistance. Our perspective is to reduce the surface roughness while maintaining a large grain size. Progress was made in modifying the morphology, grain size and roughness by variation of substrate temperature and growth rate. Furthermore investigations on texturing-dependent cell-performance were started. As for the CdTe-layer similar behaviour depending on the surface roughness is observed for the CdS-layer. Hole CdS leads to direct contact of CdTe with the TCO, resulting in a low V<sub>oc</sub>.

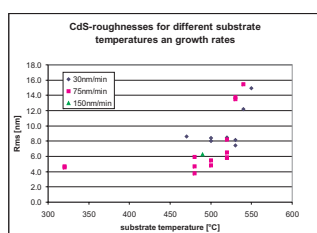


left: formation of shunts due to a high surface roughness and bad texturing  
right: highly orientated, smooth CdTe-layer ensure uniform etching without shuntformation at grainboundaries. This allows reduction in CdTe-layerthicknesses.

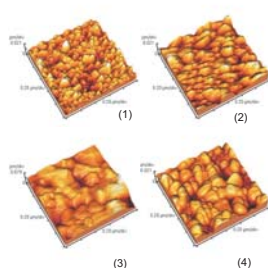


XRD-patterns for CdTe-layers deposited at different substrate temperatures and growth rates. For cooler substrates CdTe growth up strongly (111)-orientated. With increasing substrate temperature the preferred orientation switches to (220) and (311)-direction. It seems that higher deposition rates also influence the orientation to a more likely (111)-direction.

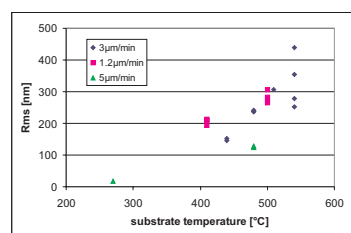
## III. Morphology of CSS-CdS and CdTe Films



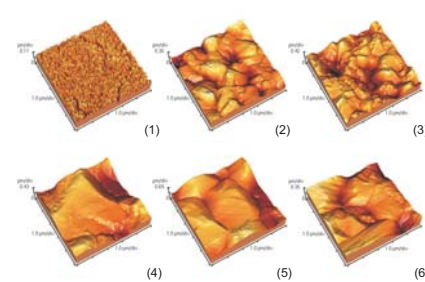
- AFM-measurements on CdS-layers with similar thicknesses (d=150nm). CdS was deposited on SnO<sub>2</sub>/In<sub>2</sub>O<sub>3</sub>-coated borosilicate glass.
- almost constant roughness for substrate temperatures up to 520°C
  - abrupt rise of roughness for temperatures above 520°C
  - decreasing roughnesses for increasing growth rate



AFM-pictures of CdS-layers deposited with different substrate temperatures and growth rates. (1): T<sub>sub</sub>=300°C, r<sub>g</sub>=75nm/min; (2): T<sub>sub</sub>=520°C, r<sub>g</sub>=75nm/min; (3): T<sub>sub</sub>=550°C, r<sub>g</sub>=75nm/min; (4): T<sub>sub</sub>=520°C, r<sub>g</sub>=150nm/min

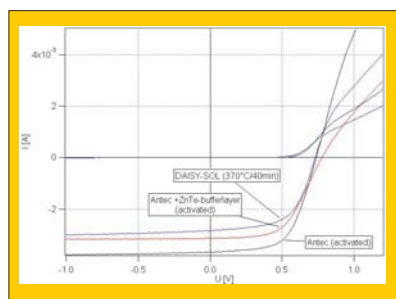


- AFM-measurements on CdTe-layers with similar thickness (d=5µm). The roughness strongly depend on substrate temperatures and growth rates.
- increasing roughness for decreasing growth rates
  - high spreading in roughnesses for high temperatures
  - very smooth, almost mirroring, black colored layers for very low temperatures



AFM-pictures of CdTe-layers deposited with different substrate temperatures and growth rates. (1): T<sub>sub</sub>=270°C, r<sub>g</sub>=5µm/min; (2): T<sub>sub</sub>=480°C, r<sub>g</sub>=5µm/min; (3): T<sub>sub</sub>=440°C, r<sub>g</sub>=3µm/min; (4): T<sub>sub</sub>=510°C, r<sub>g</sub>=3µm/min; (5): T<sub>sub</sub>=520°C, r<sub>g</sub>=1,2µm/min; (6): T<sub>sub</sub>=500°C, r<sub>g</sub>=1,2µm/min

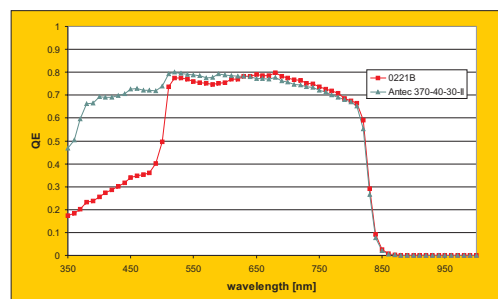
## IV. Electrical and Optical Characterisation



	DAISY-SOL cell	Antec-cell +ZnTe-layer	Antec-cell activated
(%)	8.34	8.48	11.07
V <sub>oc</sub> (V)	0.73	0.776	0.736
J <sub>sc</sub> (mA/cm <sup>2</sup> )	19.37	19.68	25.1
FF (%)	59	55.5	59.9

### J/V-plots of activated CdTe-solar-cells

The plots labeled with ANTEC-cell refer to cells cut out from a module out of ANTEC-production. One cell was covered with a ZnTe buffer layer before activation and backcontact-formation. The activation process (in a tube furnace) was the same for all cells (T: 370°C, t: 40min). As backcontact we used sputtered gold. The completely self deposited cell and the standard ANTEC-cell show similar voltages and fill-factors but slightly different currents what may be due to different CdS-layer thicknesses. The ANTEC-cell with the ZnTe-layer shows a much higher voltage but low voltage and a high series resistance which may be because of an insufficient conductivity of the ZnTe-layer.



**Quantum efficiency of DAISY-SOL solar cells vs. ANTEC-cells**  
The quantum efficiencies of both cells show good consistency for wavelengths above the CdS-absorption edge (~510nm). The high values for the QE below 510nm for ANTEC-cells may explain the higher